

Section 25

Bipolar Junction Transistor – Design

25.6 Short base transport

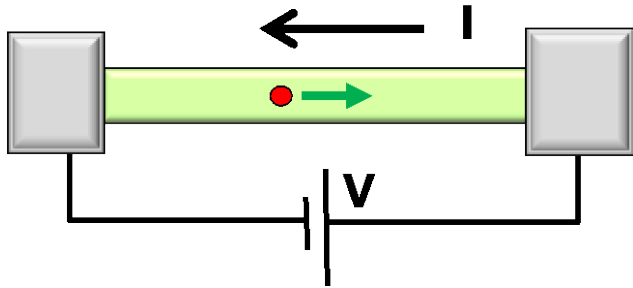
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School of Electrical and
Computer Engineering

Section 25

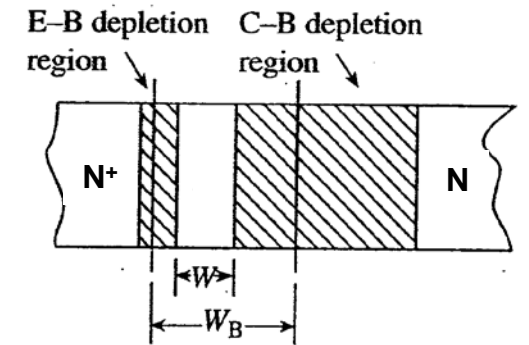
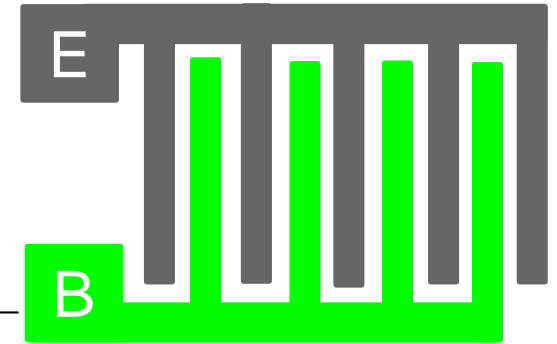
Bipolar Junction Transistor - Design



$$I = G \times V$$

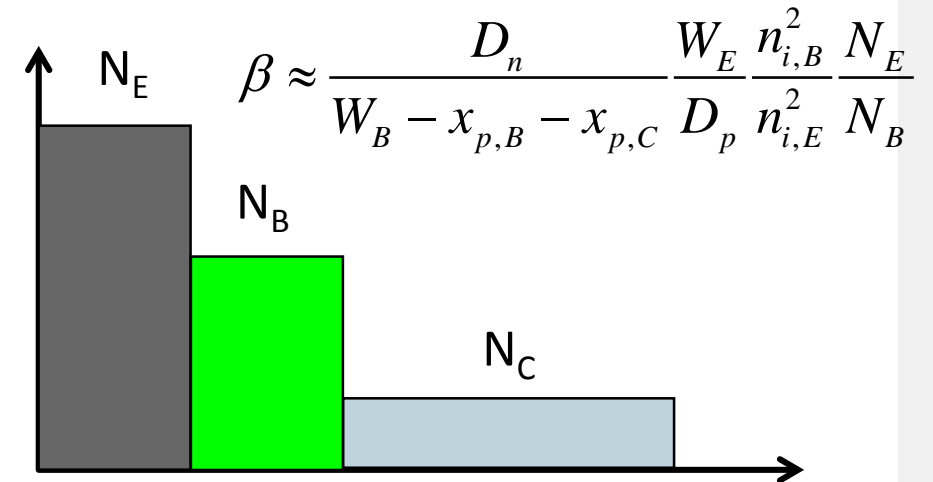
$$= q \times n \times v \times A$$

↑ charge density
 ↑ velocity
 area



$$x_{p, BE} = \sqrt{\frac{2k_s \epsilon_0}{q} \frac{N_E}{N_B (N_E + N_B)} (V_{bi} - V_{BE})}$$

$$x_{p, BC} = \sqrt{\frac{2k_s \epsilon_0}{q} \frac{N_C}{N_B (N_C + N_B)} (V_{bi} - V_{BC})}$$

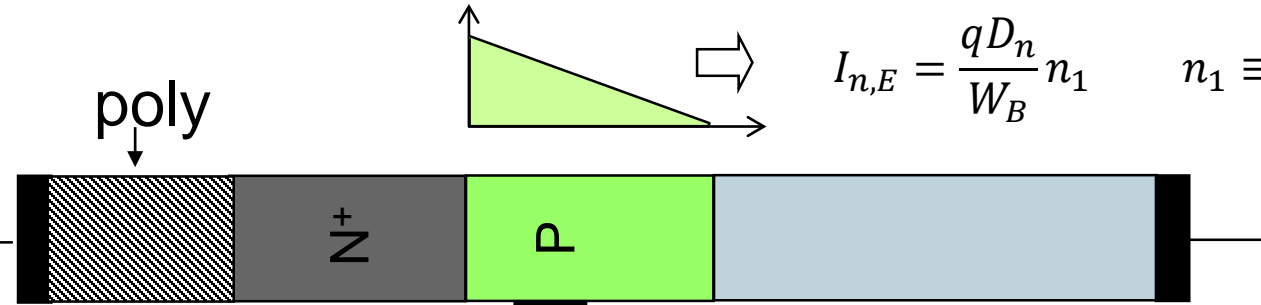


- > • 25.1 Current gain in BJTs
- > • 25.2 Base Doping Design
 - » Current Crowding – Non-Uniform Turn-On
 - » Punch-through
 - » Base Width Modulation
- > • 25.3 Collector Doping Design (Kirk Effect, Base Pushout)
- > • 25.4 Emitter Doping Design
- > • 25.5 Poly-Si emitter
- > • 25.6 Short base transport ← status

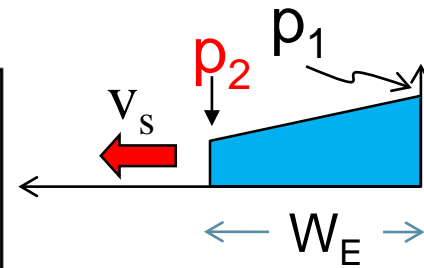
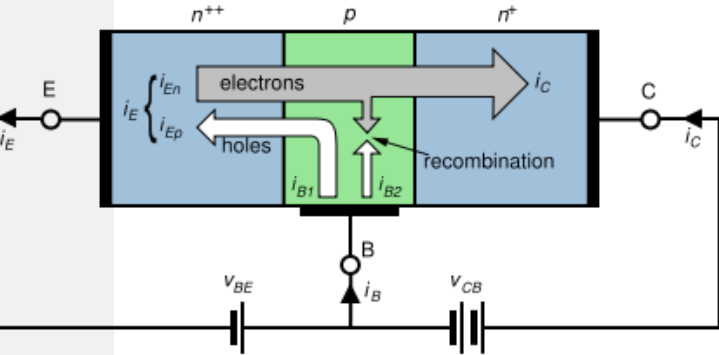
$$V_A = -\frac{qN_B W_B}{C_{CB}} \quad C_{CB} = \frac{K_s \epsilon_0}{x_{n,C} + x_{p,B}}$$

Poly-silicon Emitter + Graded Base

$$\frac{I_{B,poly}}{I_{B,Si}} = \frac{v_s}{\frac{D_p}{W_E} + v_s}$$



$$I_{n,E} = \frac{qD_n}{W_B} n_1 \quad n_1 \equiv \frac{n_{i,B}^2}{N_B} (e^{qV_{BE}\beta} - 1)$$

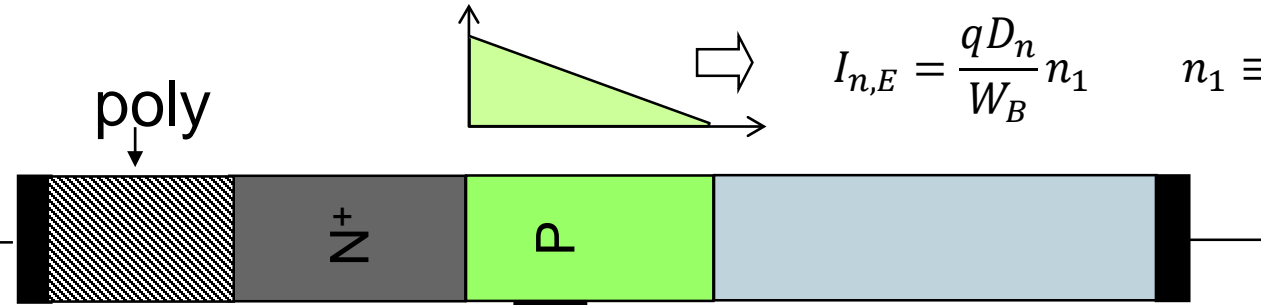


$$\beta_{poly} \sim \frac{D_n}{W_B} \frac{n_{i,B}^2}{n_{i,E}^2} \frac{N_E}{N_B} \times \frac{1}{v_s}$$

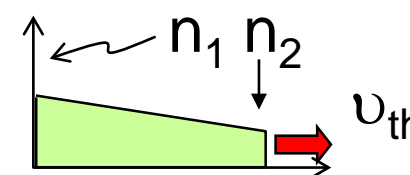
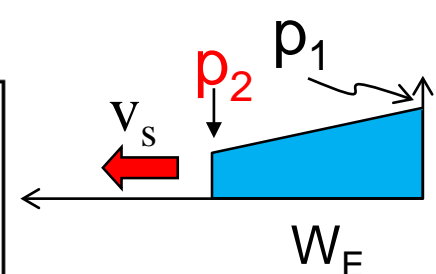
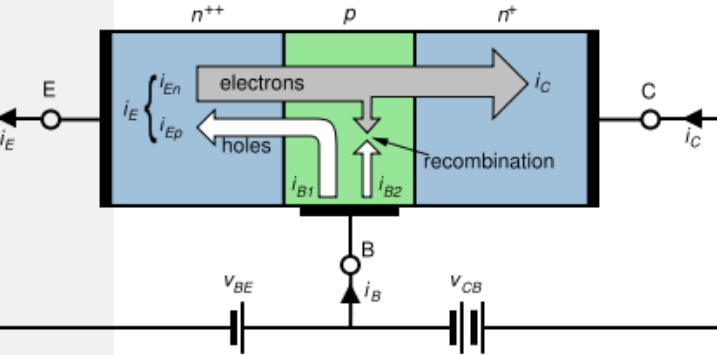
Graded Base transport

Poly-silicon Emitter + Graded Base

$$\frac{I_{B,poly}}{I_{B,Si}} = \frac{v_s}{\frac{D_p}{W_E} + v_s}$$



$$I_{n,E} = \frac{qD_n}{W_B} n_1 \quad n_1 \equiv \frac{n_{i,B}^2}{N_B} (e^{qV_{BE}\beta} - 1)$$



What if W_B becomes very short?

$$\frac{D_n}{W_B} = v_{diff} > v_{th}$$

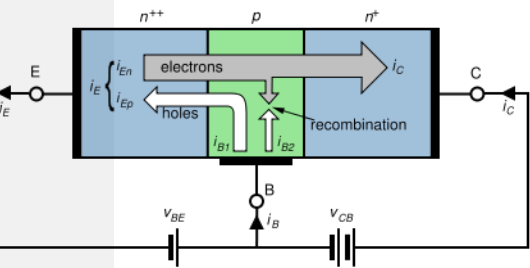
$$n_2 > 0$$

$$I_{n,E} = -qD_n \frac{n_1 - n_2}{W_B} = -qv_{th}n_2$$

$$\frac{n_2}{n_1} = \frac{D_n/W_B}{D_n/W_B + v_{th}}$$

$$\frac{I_{n,E,ballistic}}{I_{n,E,si}} = \frac{v_{th}}{\frac{D_n}{W_B} + v_{th}}$$

Gain in **short-base** Poly-silicon Transistor

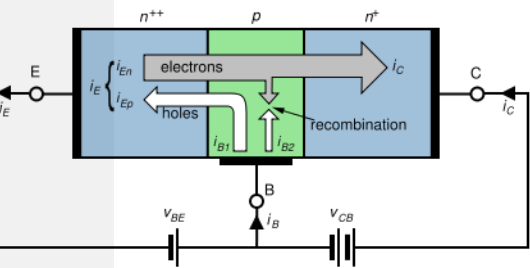


$$\frac{I_{n,E,ballistic}}{I_{n,E,si}} = \frac{v_{th}}{\frac{D_n}{W_B} + v_{th}}$$

$$\frac{I_{B,poly}}{I_{B,si}} = \frac{v_s}{\frac{D_p}{W_E} + v_s}$$

$$\beta_{poly,ballistic} = \frac{I_{C,ballistic}}{I_{B,poly}}$$

Gain in **short-base** Poly-silicon Transistor



$$\frac{I_{n,E,ballistic}}{I_{n,E,si}} = \frac{v_{th}}{\frac{D_n}{W_B} + v_{th}}$$

$$\frac{I_{B,poly}}{I_{B,si}} = \frac{v_s}{\frac{D_p}{W_E} + v_s}$$

$$\beta_{poly,ballistic} = \frac{I_{C,ballistic}}{I_{B,poly}} = \left[\frac{I_{C,ballistic}}{I_{C,si}} \right] \times \left[\frac{I_{C,si}}{I_{B,si}} \right] \times \left[\frac{I_{B,si}}{I_{B,poly}} \right]$$

$$\approx \left[\frac{v_{th}}{D_n/W_B + v_{th}} \right] \times \left[\frac{D_n}{W_B} \frac{W_E}{D_p} \frac{n_{i,B}^2}{n_{i,E}^2} \frac{N_E}{N_B} \right] \times \left[\frac{D_p/W_E + v_s}{v_s} \right]$$

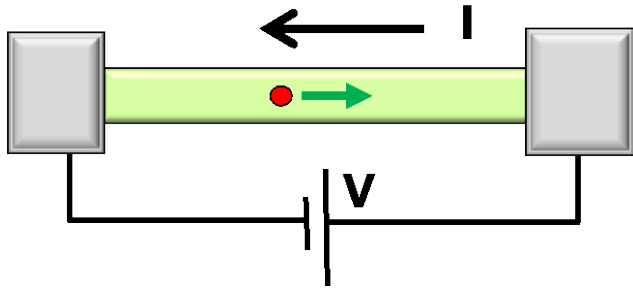
Assume small v_{th} Compared to diffusion velocity

$$\rightarrow \frac{n_{i,B}^2}{n_{i,E}^2} \times \frac{N_E}{N_B} \times \frac{v_{th}}{v_s}$$

v_s Assume small

Large devices, finite diffusion length \Rightarrow small diffusion velocity
 \Rightarrow thermal velocity is large \Rightarrow neglect diffusion velocity
 Quasi-Ballistic transport in very short base limits the gain ...

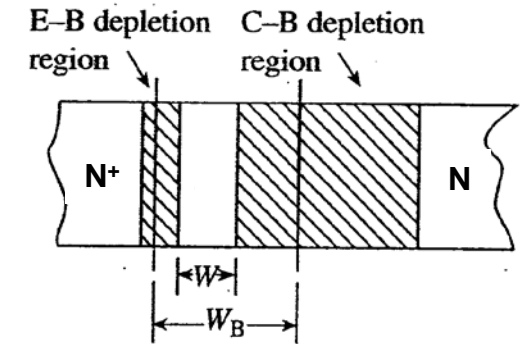
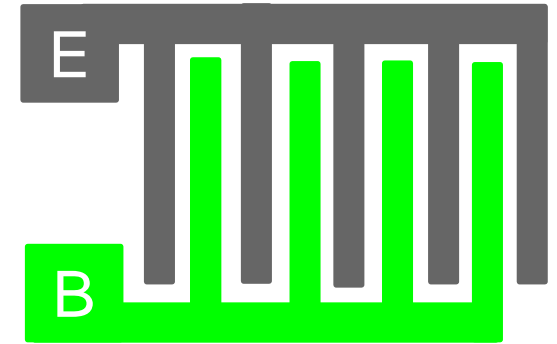
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$$V_A = -\frac{q N_B W_B}{C_{CB}}$$

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